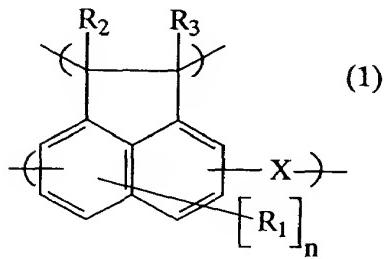


ABSTRACT OF THE DISCLOSURE

An anti-reflection coating-forming composition is provided. This composition includes a polymer and a solvent. The polymer  
5 has a structural unit represented by the formula (1):



wherein R<sub>1</sub> is a monovalent atom other than a hydrogen atom or a monovalent group, and n is an integer of 0-4, provided that when n is an integer of 2-4, a plural number of R<sub>1</sub>'s are the same or different; R<sub>2</sub> and R<sub>3</sub> are each a monovalent atom or group; and X is a bivalent group. The anti-reflection coating formed from this composition has a high antireflective effect, does not generate intermixing with a resist film, and enables a good resist pattern profile excellent in resolution and precision in cooperation with a positive or negative resist.

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